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 NEWS 8 AUG 18 FROSTI and KOSMET enhanced with Simultaneous Left and Right Truncation
 NEWS 9 AUG 18 Simultaneous left and right truncation added to ANABSTR
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 NEWS 11 SEP 25 INPADOC: Legal Status data to be reloaded
 NEWS 12 SEP 29 DISSABS now available on STN
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 NEWS 14 OCT 21 BIOSIS file reloaded and enhanced
 NEWS 15 OCT 28 BIOSIS file segment of TOXCENTER reloaded and enhanced

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```
=> s phenol novolak resin#
L1      1102 PHENOL NOVOLAK RESIN#

=> s 11 and phenol and aldehyde and oxalic and catalyst#
L2      89 L1 AND PHENOL AND ALDEHYDE AND OXALIC AND CATALYST#

=> s 12 and temperature# and pressure#
L3      81 L2 AND TEMPERATURE# AND PRESSURE#

=> s 13 and ortho ratio#
L4      1 L3 AND ORTHO RATIO#

=> d
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L4 ANSWER 1 OF 1 USPATFULL on STN

Full Text	References
AN 2002:172464	USPATFULL
TI Method of producing novolak resin	
IN Saito, Noriaki, Toyonaka-shi, JAPAN	
Aizu, Ichishi, Niihama-shi, JAPAN	
Nakajima, Nobuyuki, Niihama-shi, JAPAN	
Fujiwara, Masahiro, Niihama-shi, JAPAN	
Yano, Koji, Niihama-shi, JAPAN	
PA SUMITOMO CHEMICAL COMPANY, LIMITED (non-U.S. corporation)	
PI US 2002091224	A1 20020711
AI US 2001-364	A1 20011204 (10)
PRAI JP 2000-377258	20001212
JP 2000-377259	20001212
JP 2001-153632	20010523
DT Utility	
FS APPLICATION	
LN.CNT 579	
INCL INCLM: 528/129.000	
NCL NCLM: 528/129.000	
IC [7]	
ICM: C08G008-04	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

```
=> s 13 and ortho
L5      25 L3 AND ORTHO

=> s 15 and (ortho-cresol or o-cresol)

L6      14 L5 AND (ORTHO-CRESOL OR O-CRESOL)

=> d 16 1-14
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L6 ANSWER 1 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full Text	References
PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET	
AN 720052	EUROPATFULL UP 19970408 EW 199627 FS OS STA R
TIEN Photosensitive composition and photosensitive lithographic printing plate.	
TIDE Photoempfindliche Zusammensetzung und photolithographische Druckplatte.	
TIFR Composition photosensible et plaque d'impression photolithographique.	
IN Matsuo, Fumijuku, Yokohama Research Center, Mitsubishi Chemical Corp.,	

1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP;
 Kanazawa, Daisuke, Yokohama Research Center, Mitsubishi Chemical Corp.,
 1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP;
 Sasaki, Mitsuru, Yokohama Research Center, Mitsubishi Chemical Corp.,
 1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP;
 Matsubara, Shinichi, Konica Corp., 1, Sakura-machi, Hino-shi, Tokyo, JP;
 Higashino, Katsuhiko, Konica Corp., 1, Sakura-machi, Hino-shi, Tokyo,
 JP;
 Yokoo, Toshiaki, Yokohama Research Center, Mitsubishi Chemical Corp.,
 1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP
 PA Mitsubishi Chemical Corporation, 5-2 Marunouchi 2-chome, Chiyoda-ku,
 Tokyo, JP KONICA CORPORATION, No. 1 Sakura-machi, Hino-shi Tokyo, JP
 SO Wila-EPZ-1996-H27-T2a
 DS R DE; R FR; R GB; R NL
 PIT EPA1 EUROPÄISCHE PATENTANMELDUNG
 PI EP 720052 A1 19960703
 OD 19960703
 AI EP 1995-119982 19951218
 PRAI JP 1994-337070 19941227
 JP 1995-692 19950106
 IC ICM G03F007-023

L6 ANSWER 2 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 660187 EUROPATFULL UP 19991205 EW 199526 FS OS STA B
 TIEN Radiation-sensitive resin composition.
 TIDE Strahlungsempfindliche Harzzusammensetzung.
 TIFR Composition a base de resine, sensible aux radiations.
 IN Yamachika, Mikio, 15-1-1105, Taichimaru, Kuwana-shi, JP;
 Kobayashi, Eiichi, 535 Pierce St. No.336, Albany, CA 94706, US;
 Ota, Toshiyuki, 208, Unemegaoka-4-chome, Yokkaichi-shi, JP;
 Tsuji, Akira, 3-7, Hagigaokacho, Yokkaichi-shi, JP
 PA JAPAN SYNTHETIC RUBBER CO., LTD., 11-24, Tsukiji-2-chome Chuo-ku, Tokyo
 104, JP
 SO Wila-EPZ-1995-H26-T2a
 DS R DE; R FR; R GB; R IT; R NL
 PIT EPA1 EUROPÄISCHE PATENTANMELDUNG
 PI EP 660187 A1 19950628
 OD 19950628
 AI EP 1994-309457 19941216
 PRAI JP 1993-345792 19931224
 JP 1994-268112 19941007
 IC ICM G03F007-039

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 660187 EUROPATFULL ED 19970414 EW 199710 FS PS
 TIEN Radiation-sensitive resin composition.
 TIDE Strahlungsempfindliche Harzzusammensetzung.
 TIFR Composition a base de resine, sensible aux radiations.
 IN Yamachika, Mikio, 15-1-1105, Taichimaru, Kuwana-shi, JP;
 Kobayashi, Eiichi, 535 Pierce St. No.336, Albany, CA 94706, US;
 Ota, Toshiyuki, 208, Unemegaoka-4-chome, Yokkaichi-shi, JP;
 Tsuji, Akira, 3-7, Hagigaokacho, Yokkaichi-shi, JP
 PA JAPAN SYNTHETIC RUBBER CO., LTD., 11-24, Tsukiji-2-chome Chuo-ku, Tokyo
 104, JP
 SO Wila-EPS-1997-H10-T2
 DS R DE; R FR; R GB; R IT; R NL
 PIT EPB1 EUROPÄISCHE PATENT-SCHRIFT
 PI EP 660187 B1 19970305

OD 19950628
 AI EP 1994-309457 19941216
PRAI JP 1993-345792 19931224
 JP 1994-268112 19941007
 REN DATABASE WPI Section Ch, Week 9323, Derwent Publications Ltd., London,
 GB; Class A89, AN 93-185601 &
 JP-A-5113667 (MITSUBISHI ELECTRIC CORP) 7 May 1993 DATABASE WPI Section
 Ch, Week 9322, Derwent Publications Ltd., London, GB; Class A13, AN
 93-177961 &
 JP-A-5107757 (CANON KK) 30 April 1993
 IC ICM G03F007-039

L6 ANSWER 3 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 591984 EUROPATFULL UP 20000216 EW 199415 FS OS STA B
 TIEN Resin composition for aqueous paint.
 TIDE Harzzusammensetzung fuer einen waessrigen Anstrich.
 TIFR Composition de resine pour une peinture aqueuse.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP;
 Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPZ-1994-H15-T1a
 DS R DE; R GB
 PIT EPA1 EUROPAEISCHE PATENTANMELDUNG
 PI EP 591984 A1 19940413
 OD 19940413
 AI EP 1993-116319 19931008
PRAI JP 1992-297953 19921009
 JP 1993-32538 19930129
 JP 1993-32587 19930129
 IC ICM C09D005-44
 ICS C08G059-64

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 591984 EUROPATFULL ED 19970727 EW 199728 FS PS
 TIEN Resin composition for aqueous paint.
 TIDE Harzzusammensetzung fuer einen waessrigen Anstrich.
 TIFR Composition de resine pour une peinture aqueuse.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP;
 Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPS-1997-H28-T1
 DS R DE; R GB
 PIT EPB1 EUROPAEISCHE PATENTSCHRIFT
 PI EP 591984 B1 19970709
 OD 19940413
 AI EP 1993-116319 19931008
PRAI JP 1992-297953 19921009
 JP 1993-32538 19930129
 JP 1993-32587 19930129
REP EP 356970 A EP 444710 A
 US 5091446 A
 IC ICM C09D005-44
 ICS C08G059-64

L6 ANSWER 4 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 567066 EUROPATFULL ED 20000416 EW 199343 FS OS STA B
 TIEN Resin composition for aqueous paints.
 TIDE Harzzusammensetzung fuer waessrige Lacke.
 TIFR Composition de resine pour des peintures aqueuses.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP;
 Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPZ-1993-H43-T1a
 DS R DE; R GB
 PIT EPA2 EUROPAEISCHE PATENTANMELDUNG
 PI EP 567066 A2 19931027
 OD 19931027
 AI EP 1993-106378 19930420
 PRAI JP 1992-129740 19920424
 IC ICM C09D005-44
 ICS C09D163-00 C08G059-62 C08G059-64

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 567066 EUROPATFULL UP 20000723 EW 200028 FS PS
 TIEN Resin composition for aqueous paints.
 TIDE Harzzusammensetzung fuer waessrige Lacke.
 TIFR Composition de resine pour des peintures aqueuses.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP;
 Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPS-2000-H28-T1
 DS R DE; R GB
 PIT EPB1 EUROPAEISCHE PATENTSCHRIFT
 PI EP 567066 B1 20000712
 OD 19931027
 AI EP 1993-106378 19930420
 PRAI JP 1992-129740 19920424
 REF EP 127915 A EP 135811 A
 EP 352671 A EP 396912 A
 EP 591984 A
 IC ICM C09D005-44
 ICS C09D163-00 C08G059-62 C08G059-64 C08G059-32

L6 ANSWER 5 OF 14 USPATFULL on STN

Full Text	Citing References
AN 2002:172464 USPATFULL	
TI Method of producing novolak resin	
IN Saito, Noriaki, Toyonaka-shi, JAPAN	
Aizu, Ichishi, Niihama-shi, JAPAN	
Nakajima, Nobuyuki, Niihama-shi, JAPAN	
Fujiwara, Masahiro, Niihama-shi, JAPAN	
Yano, Koji, Niihama-shi, JAPAN	
PA SUMITOMO CHEMICAL COMPANY, LIMITED (non-U.S. corporation)	
PI US 2002091224 A1 20020711	
AI US 2001-364 A1 20011204 (10)	
PRAI JP 2000-377258 20001212	
JP 2000-377259 20001212	
JP 2001-153632 20010523	
DT Utility	
FS APPLICATION	
LN.CNT 579	
INCL INCLM: 528/129.000	
NCL INCLM: 528/129.000	
IC [7]	
ICM: C08G008-04	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 6 OF 14 USPATFULL on STN

	Full Text	Citing References
AN	2001:165552	USPATFULL
TI	Phenol novolak resin, production process thereof, and positive photoresist composition using the same	
IN	Miyagi, Ken, Kanagawa, Japan Ohuchi, Yasuhide, Kanagawa, Japan Hirata, Atsuko, Kanagawa, Japan Doi, Kousuke, Kanagawa, Japan Kohara, Hidekatsu, Kanagawa, Japan Nakayama, Toshimasa, Kanagawa, Japan	
PI	US 2001024762	A1 20010927
AI	US 2001-793958	A1 20010228 (9)
PRAI	JP 2000-53503	20000229
	JP 2000-53504	20000229
	JP 2000-53505	20000229
DT	Utility	
FS	APPLICATION	
LN.CNT	1209	
INCL	INCLM: 430/192.000 INCLS: 430/165.000; 430/191.000; 430/193.000; 430/326.000; 528/155.000; 528/144.000	
NCL	NCLM: 430/192.000 NCLS: 430/165.000; 430/191.000; 430/193.000; 430/326.000; 528/155.000; 528/144.000	
IC	[7] ICM: G03F007-023 ICS: C08G014-04; G03F007-30	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 7 OF 14 USPATFULL on STN

	Full Text	Citing References
AN	1998:4379	USPATFULL
TI	Positive resin composition sensitive to ultraviolet rays	
IN	Kawabe, Yasumasa, Haibara-gun, Japan Yamanaka, Tsukasa, Haibara-gun, Japan Aoi, Toshiaki, Haibara-gun, Japan	
PA	Fuji Photo Film Co., LTD., Kanagawa, Japan (non-U.S. corporation)	
PI	US 5707776	19980113
AI	US 1995-438481	19950510 (8)
PRAI	JP 1994-98671	19940512
DT	Utility	
FS	Granted	
LN.CNT	1881	
INCL	INCLM: 430/270.100 INCLS: 430/920.000; 430/921.000; 430/905.000; 430/171.000; 430/176.000; 522/166.000	
NCL	NCLM: 430/270.100 NCLS: 430/171.000; 430/176.000; 430/905.000; 430/920.000; 430/921.000; 522/166.000	
IC	[6] ICM: G03C001-73	
EXF	430/270; 430/920; 430/921; 430/905; 430/171; 430/176; 522/166	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 8 OF 14 USPATFULL on STN

	Full Text	Citing References
AN	97:59033	USPATFULL
TI	Photosensitive composition and photosensitive lithographic printing	

plate
IN Matsuo, Fumiyuki, Yokohama, Japan
Kanazawa, Daisuke, Yokohama, Japan
Sasaki, Mitsuru, Yokohama, Japan
Matsubara, Shinichi, Hino, Japan
Higashino, Katsuhiko, Hino, Japan
Yokoo, Toshiaki, Yokohama, Japan
PA Mitsubishi Chemical Corporation, Tokyo, Japan (non-U.S. corporation)
Konica Corporation, Tokyo, Japan (non-U.S. corporation)
PI US 5645969 19970708
AI US 1995-576136 19951221 (8)
PRAI JP 1994-337070 19941227
JP 1995-692 19950106
DT Utility
FS Granted
LN.CNT 1292
INCL INCLM: 430/165.000
INCLS: 430/190.000; 430/191.000; 430/192.000; 430/193.000; 528/137.000;
528/139.000
NCL NCLM: 430/165.000
NCLS: 430/190.000; 430/191.000; 430/192.000; 430/193.000; 528/137.000;
528/139.000
IC [6]
ICM: G03F007-023
EXF 430/190; 430/165; 430/192; 430/193; 430/191; 528/137; 528/139
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 9 OF 14 USPATFULL on STN

Full Text	Citing References
AN 96:85015 USPATFULL	
TI Radiation sensitive resin composition comprising copolymer of isopropenylphenol and T-butyl(meth)acrylate	
IN Yamachika, Mikio, Kuwana, Japan Kobayashi, Eiichi, Albany, CA, United States Ota, Toshiyuki, Yokkaichi, Japan Tsuji, Akira, Yokkaichi, Japan	
PA Japan Synthetic Rubber Co., Ltd., Tokyo, Japan (non-U.S. corporation)	
PI US 5556734 19960917	
AI US 1994-363269 19941223 (8)	
PRAI JP 1993-345792 19931224	
JP 1994-268112 19941007	
DT Utility	
FS Granted	
LN.CNT 1357	
INCL INCLM: 430/270.100	
INCLS: 430/192.000; 430/910.000; 430/921.000	
NCL NCLM: 430/270.100	
NCLS: 430/192.000; 430/910.000; 430/921.000	
IC [6] ICM: G03C001-73	
EXF 430/270; 430/326; 430/192; 430/910; 430/921	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.	

L6 ANSWER 10 OF 14 USPATFULL on STN

Full Text	Citing References
AN 95:33997 USPATFULL	
TI Resin composition for aqueous paint	
IN Fujibayahsi, Toshio, Hadano, Japan Nagaoka, Haruo, Hiratsuka, Japan	
PA Kansai Paint Co., Ltd., Hyogo, Japan (non-U.S. corporation)	
PI US 5407748 19950418	
AI US 1993-133363 19931008 (8)	

PRAI JP 1992-297953 19921009
 JP 1993-32538 19930129
 JP 1993-32587 19930129
 DT Utility
 FS Granted
 LN.CNT 2215
 INCL INCLM: 428/418.000
 INCLS: 523/404.000; 523/414.000; 525/407.000; 525/409.000
 NCL NCLM: 428/418.000
 NCLS: 523/404.000; 523/414.000; 525/407.000; 525/409.000
 IC [6]
 ICM: B32B015-08
 EXF 428/418; 523/404; 523/414; 525/407; 525/409
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 11 OF 14 USPATFULL on STN

Full Text	Citing References
AN 94:104621 USPATFULL	
TI Resin composition for aqueous paints	
IN Fujibayashi, Toshio, Hadano, Japan Nagaoka, Haruo, Hiratsuka, Japan	
PA Kansai Paint Co., Ltd., Hyogo, Japan (non-U.S. corporation)	
PI US 5369151 19941129	
AI US 1993-120787 19930915 (8)	
RLI Division of Ser. No. US 1993-48512, filed on 20 Apr 1993	
DT Utility	
FS Granted	
LN.CNT 1396	
INCL INCLM: 523/414.000 INCLS: 204/181.400; 204/181.700; 428/418.000	
NCL NCLM: 523/414.000 NCLS: 204/503.000; 204/504.000; 204/505.000; 428/418.000	
IC [5] ICM: C08K003-20 ICS: C08L063-04	
EXF 523/414; 204/181.4; 204/181.7; 428/418	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.	

L6 ANSWER 12 OF 14 USPATFULL on STN

Full Text	Citing References
AN 94:104620 USPATFULL	
TI Resin composition for aqueous paints	
IN Fujibayashi, Toshio, Hadano, Japan Nagaoka, Haruo, Hiratsuka, Japan	
PA Kansai Paint Co., Ltd., Hyogo, Japan (non-U.S. corporation)	
PI US 5369150 19941129	
AI US 1993-48512 19930420 (8)	
PRAI JP 1992-129740 19920424	
DT Utility	
FS Granted	
LN.CNT 1385	
INCL INCLM: 523/414.000	
NCL NCLM: 523/414.000	
IC [5] ICM: C08K003-20 ICS: C08L063-04	
EXF 523/414	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.	

L6 ANSWER 13 OF 14 USPATFULL on STN

Full Text	Citing References
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AN 93:44346 USPATFULL
 TI Phenolic resin and method for preparing same
 IN Ando, Shinji, Nagoya, Japan
 Fukui, Yukio, Nagoya, Japan
 Timuro, Shigeru, Nagoya, Japan
 PA Mitsui Toatsu Chemicals, Inc., Tokyo, Japan (non-U.S. corporation)
 PI US 5216112 19930601
 AI US 1991-745422 19910815 (7)
 PRAI JP 1990-216984 19900820
 JP 1990-216985 19900820
 JP 1990-262984 19901002
 JP 1991-39940 19910306
 DT Utility
 FS Granted
 LN.CNT 951
 INCL INCLM: 528/157.000
 INCLS: 528/129.000; 528/144.000; 528/165.000
 NCL NCLM: 528/157.000
 NCLS: 528/129.000; 528/144.000; 528/165.000
 IC [5]
 ICM: C08G008-04
 ICS: C08G014-04
 EXF 528/129; 528/165; 528/144; 528/157
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 14 OF 14 USPATFULL on STN

Full Text	Citing Reference
AN 89:87611 USPATFULL	
TI High molecular weight ortho cresol -novolak resins and process for the preparation thereof using alcoholic or acidic organic solvents	
IN Nakano, Yoshitomo, Mie, Japan Kada, Masumi, Mie, Japan	
PA Mitsubishi Petrochemical Co., Ltd., Tokyo, Japan (non-U.S. corporation)	
PI US 4876324 19891024	
AI US 1987-49335 19870513 (7)	
RLI Division of Ser. No. US 1985-741138, filed on 4 Jun 1985, now abandoned	
PRAI JP 1984-116510 19840608	
DT Utility	
FS Granted	
LN.CNT 1236	
INCL INCLM: 528/142.000 INCLS: 528/144.000	
NCL NCLM: 528/142.000 NCLS: 528/144.000	
IC [4] ICM: C08G008-12	
EXF 528/142; 528/144	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.	

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